









Superconducting COMPUTING: An energy-efficient quantum-based technology for supercomputers

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data centres (Google, Facebook,...)



Google servers - The Dalles - Oregon







Copyright Google



Energy consumption

In 2010, routers and servers consumed:

- between 1.1 % and 1.5 % of the total energy production worldwide
- between 1.7 % and 2.2 % in the United States of America





Source: Google



Need of computers with higher performance

The demand of high performance computers and servers will continue to grow. We need:

- better predictive models for climate change and weather forecast;
- to better understand the formation of the early Universe;
- to understand subatomic physics;
- to model cells, for genetics, biotechnologies;
- to simulate brain functions, ...

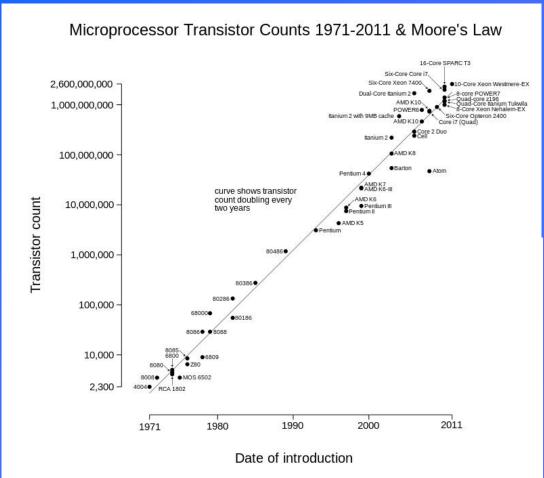


But the required power cannot follow the same pace



Pushing current technologies to the limits

Moore's law: the density of transistors per unit area of electronics chips doubles roughly every two years



2016 : Apple A10 (TSMC)

3.3 billions of transistors (FinFET)

125mm² (11mm x 11 mm)

4 cores (2 active at a time only)

Technology: 16 nm

Consumption: not released

Clock frequency: 2.34 GHz

2.64 billions of transistors/cm²

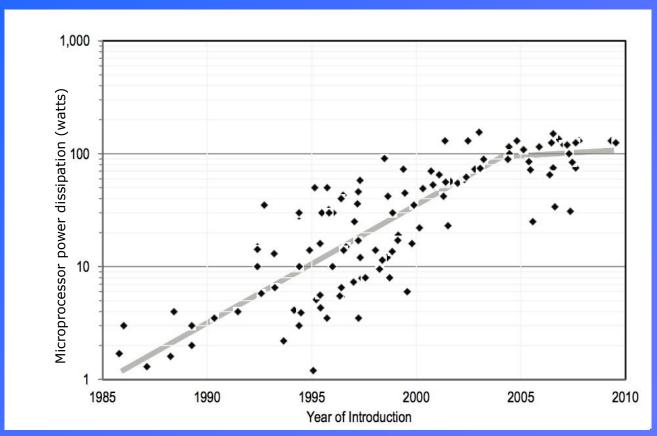




Dennard scaling law

An equivalent reduction of the power consumption per device is achieved, to keep constant the power dissipated by the chip.

1985 : 1 watt/cm² 2016 : 145 watts/cm²

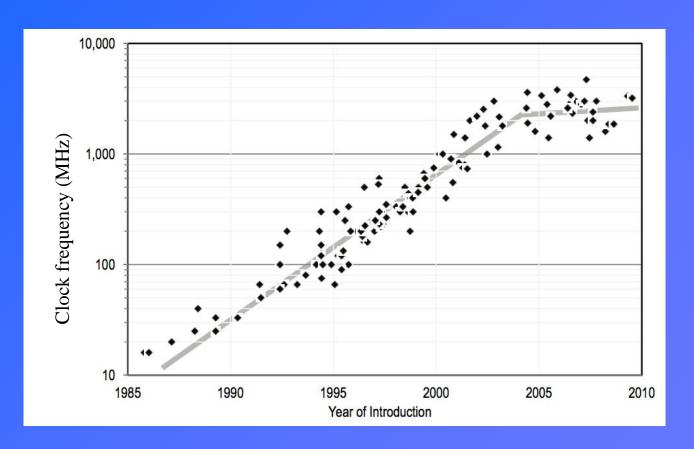


Source: THE FUTURE OF COMPUTING PERFORMANCE - Game Over or Next Level? Copyright 2011 by the National Academy of Sciences of the USA



Clock frequencies of microprocessors

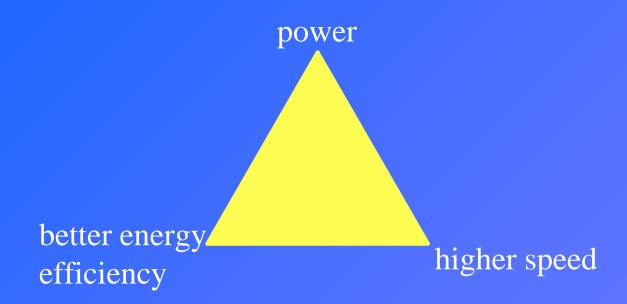
Clock frequencies of processors increased from about 10 MHz in 1985 to 3 GHz in 2005 : 40% increase of frequency each year for two decades.



Source: THE FUTURE OF COMPUTING PERFORMANCE - Game Over or Next Level? Copyright 2011 by the National Academy of Sciences of the USA



Metrics to compare technologies

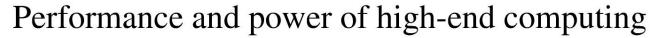


Definitions

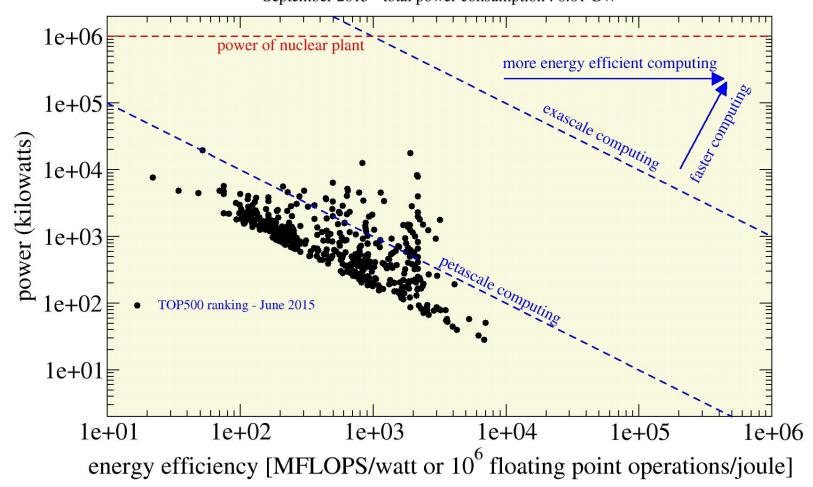
- FLOP: FLoating Point Operation
- energy efficiency = number of FLOPs per joule
- speed = number of FLOPs per second (speed means frequency of operation)

speed = power * energy efficiency



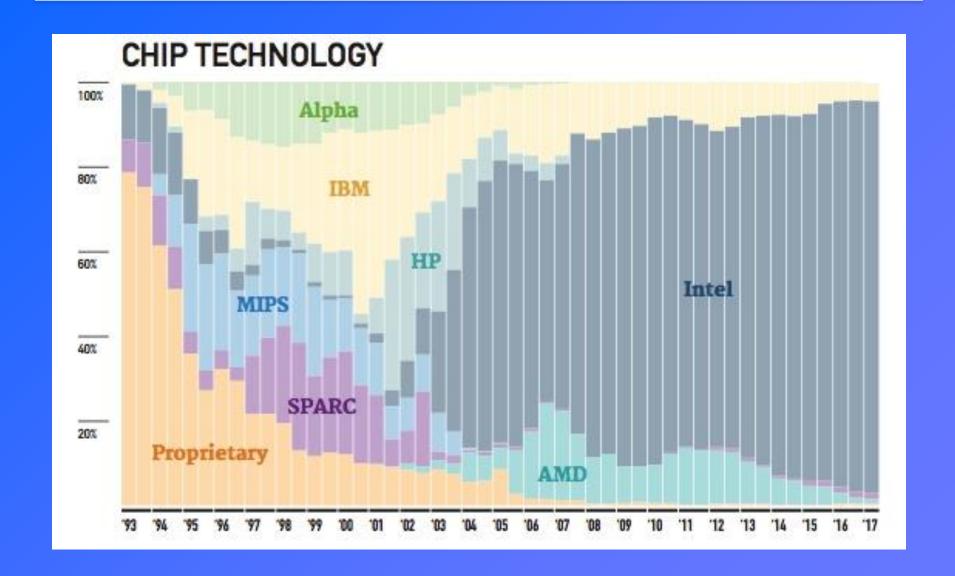


September 2015 - total power consumption : 0.61 GW





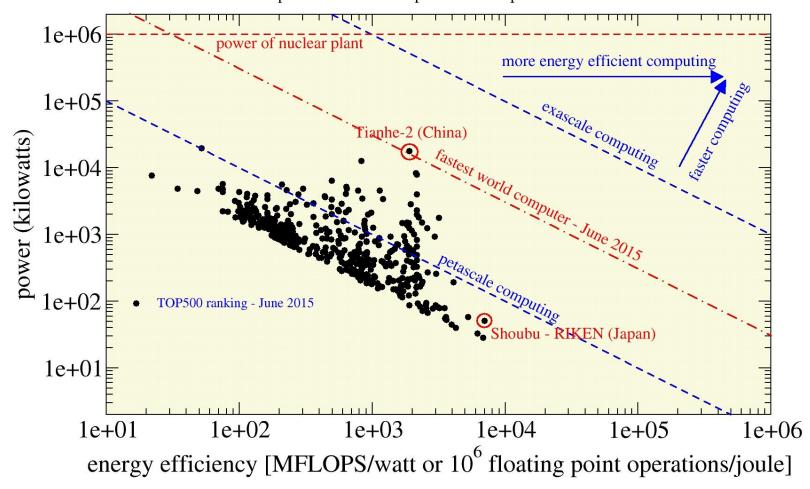
Semiconductor chips manufacturers







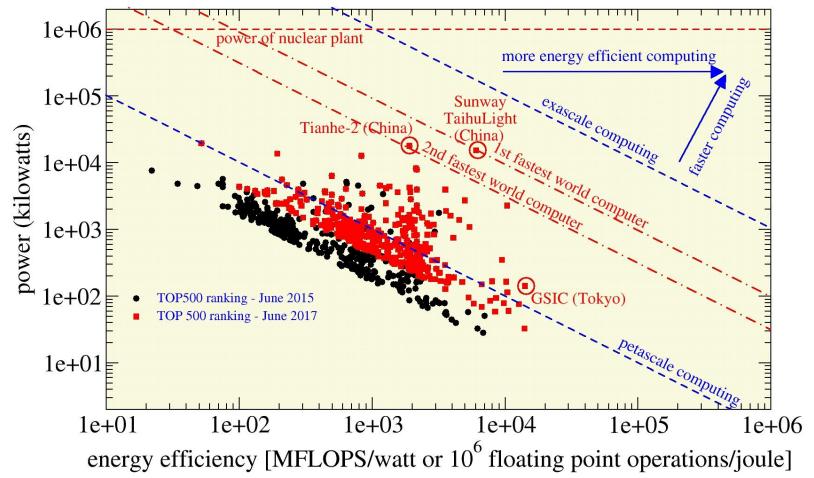
September 2015 - total power consumption : 0.61 GW







September 2017 - total power consumption : 0.65 GW







September 2017 - total power consumption: 0.65 GW 1e+06 more energy efficient computing 1e + 05power (kilowatts) 1e + 041e+03le+02 TOP 500 ranking - June 2017 TOP100 ranking - June 2017 1e+01 1e + 021e + 011e + 031e + 041e + 051e+06 energy efficiency [MFLOPS/watt or 10⁶ floating point operations/joule]

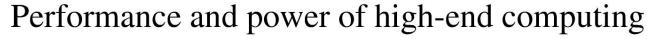




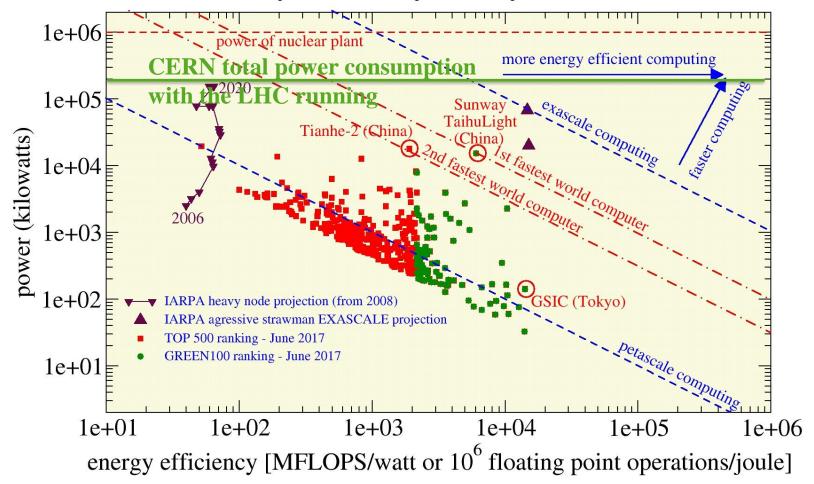
September 2017 - total power consumption: 0.65 GW 1e+06 er of nuclear plan more energy efficient computing 1e + 05power (kilowatts) 1e + 041e+03 le+02 TOP 500 ranking - June 2017 GREEN100 ranking - June 2017 1e+011e + 021e + 011e + 031e + 041e + 051e+06



energy efficiency [MFLOPS/watt or 10⁶ floating point operations/joule]



September 2017 - total power consumption : 0.65 GW





Semiconductors: energy-delay product

Semiconductors: the dynamic power is the limiting quantity:

$$P_{dd} = C V_{dd}^2 f$$

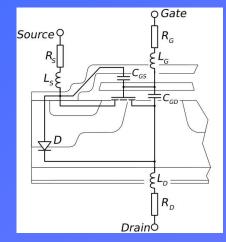
- V_{dd} is the supply voltage
- C is the intrinsic gate capacitance

The intrinsic gate delay is:
$$\tau = \frac{C V_{dd}}{I_d}$$

• *I_d* is the drain saturation current

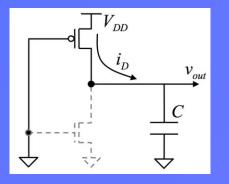
The energy-delay product (EDP) is:

$$EDP = \tau \frac{P_{dd}}{f} = \frac{C V_{dd}}{I_d} C V_{dd}^2 = \frac{C^2 V_{dd}^3}{I_d}$$



reduce transistor size

reduce supply voltage



energy-delay product (EDP) = $1/(\text{energy efficiency}^2 * \text{power}) = \text{power/speed}^2$



Semiconductors: projection for the coming decade

Summary Table of ITRS Technology Trend Targets

y (n)	2042	2015	2047	2040	2024	2002	2025	2000
Year of Production	2013	2015	2017	2019	2021	2023	2025	2028
Logic Industry "Node Name" Label	"16/14"	"10"	"7"	"5"	"3.5"	"2.5"	"1.8"	
Logic ½ Pitch (nm)	40	32	25	20	16	13	10	7
Flash ½ Pitch [2D] (nm)	18	15	13	11	9	8	8	8
DRAM ½ Pitch (nm)	28	24	20	17	14	12	10	7.7
FinFET Fin Half-pitch (new) (nm)	30	24	19	15	12	9.5	7.5	5.3
FinFET Fin Width (new) (nm)	7.6	7.2	6.8	6.4	6.1	5.7	5.4	5.0
6-t SRAM Cell Size(um2) [@60f2]	0.096	0.061	0.038	0.024	0.015	0.010	0.0060	0.0030
MPU/ASIC HighPerf 4t NAND Gate Size(um2)	0.248	0.157	0.099	0.062	0.039	0.025	0.018	0.009
4-input NAND Gate Density (Kgates/mm) [@155f2]	4.03E+03	6.37E+03	1.01E+04	1.61E+04	2.55E+04	4.05E+04	6.42E+04	1.28E+05
Flash Generations Label (bits per chip) (SLC/MLC)	64G /128G	128G /256G	256G / 512G	512G / 1T	512G / 1T	1T / 2T	2T / 4T	4T / 8T
Flash 3D Number of Layer targets (at relaxed Poly half pitch)	16-32	16-32	16-32	32-64	48-96	64-128	96-192	192-384
Flash 3D Layer half-pitch targets (nm)	64nm	54nm	45nm	30nm	28nm	27nm	25nm	22nm
DRAM Generations Label (bits per chip)	4G	8G	8G	16G	32G	32G	32G	32G
450mm Production High Volume Manufacturing Begins (100Kwspm)				2018				
Vdd (High Performance, high Vdd transistors)[**]	0.86	0.83	0.80	0.77	0.74	0.71	0.68	0.64
1/(CV/I) (1/psec) [**]	1.13	1.53	1.75	1.97	2.10	2.29	2.52	3.17
On-chip local clock MPU HP [at 4% CAGR]	5.50	5.95	6.44	6.96	7.53	8.14	8.8	9.9
Maximum number wiring levels funchanged	13	13	14	14	15	15	16	17
MPU High-Performance (HP) Printed Gate Length (GLpr) (nm) [**]	28	22	18	14	11	9	7	5
MPU High-Performance Physical Gate Length (GLph) (nm) [**]	20	17	14	12	10	8	7	5
ASIC/Low Standby Power (LP) Physical Gate Length (nm) (GLph)[**]	23	19	16	13	11	9	8	6

^{**} Note: from the PIDS working group data; however, the calibration of Vdd, GLph, and I/CV is ongoing for improved targets in 2014 ITRS work

Source: International Technology Roadmap for Semiconductors – 2013 edition – Executive summary



Energy-delay product: projection

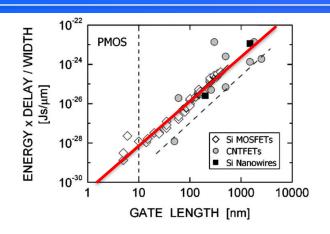


Fig. 6. Energy-delay product per device width versus transistor physical gate length of PMOS transistors.

Source: Robert Chau et al, IEEE Trans. Nanotechnology, Vol. 4, No. 2, March 2005

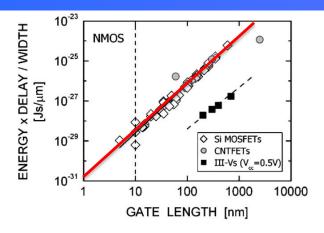


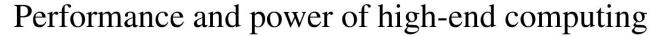
Fig. 7. Energy-delay product per device width versus transistor physical gate length of NMOS transistors.

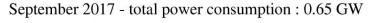
$$EDP[J \cdot s / \mu m] = 4 \cdot 10^{-31} \cdot gate \ length[nm]^{2.3}$$

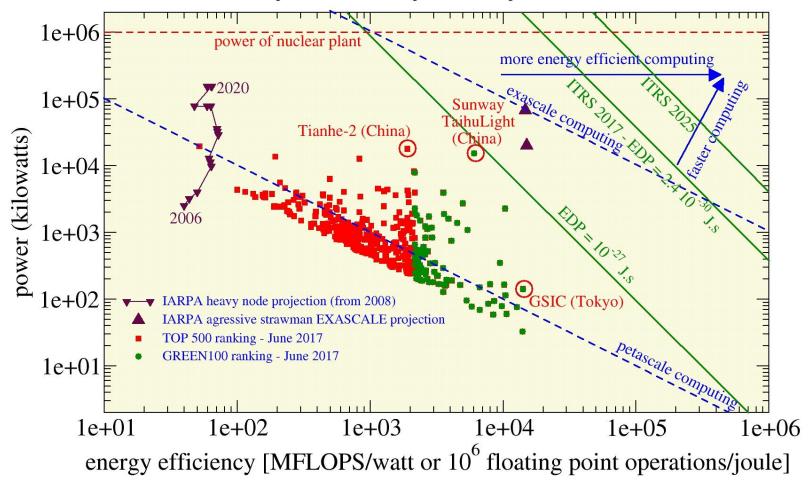
$$EDP[J \cdot s] = 4 \cdot 10^{-34} \cdot gate length[nm]^{3.3}$$

Year	gate length	EDP (J.s/μm)	EDP (J.s)
2013	20	3,9E-28	7,9E-30
2015	17	2,7E-28	4,6E-30
2017	14	1,7E-28	2,4E-30
2019	12	1,2E-28	1,5E-30
2021	10	8,0E-29	8,0E-31
2023	8	4,8E-29	3,8E-31
2025	7	3,5E-29	2,5E-31
2028	5	1,6E-29	8,1E-32
2040	1	4,0E-31	4,0E-34











Supercomputers for astronomy



Atacama Large Millimeter Array (ALMA) - Source : ESO

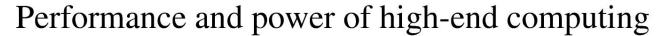


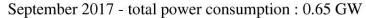
ALMA correlator

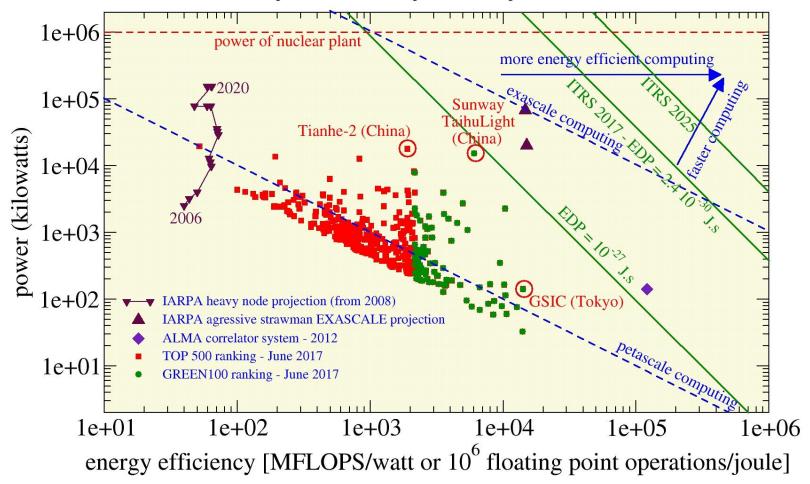


One of the four quadrants making up the ALMA correlator - Source : ESO



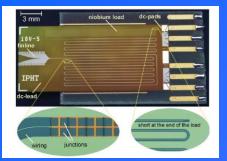




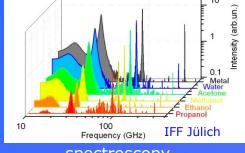




Superconducting computing with Josephson junctions



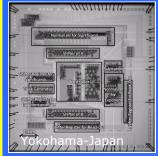
metrology



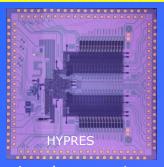
spectroscopy



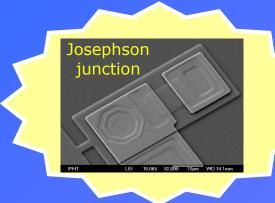
magneto-encephalography



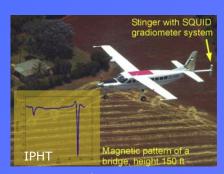
processors



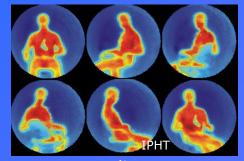
signal processing







geophysics



security

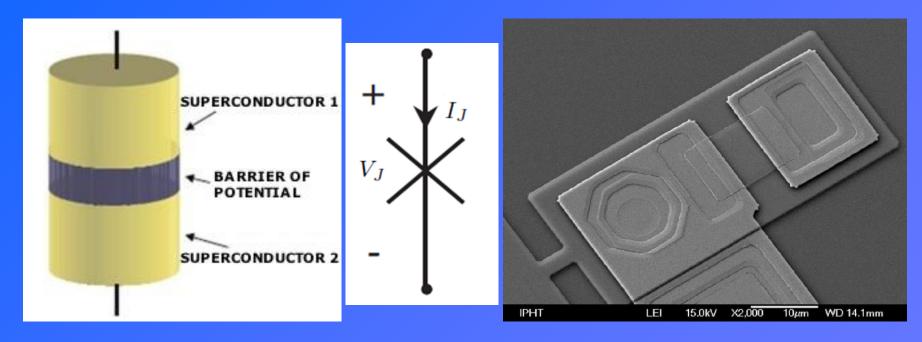


magnetic field imaging

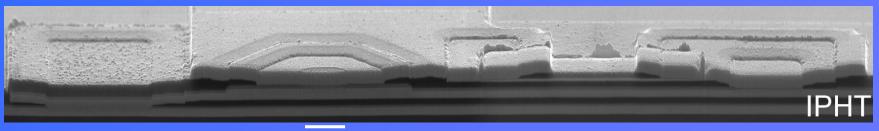


The Josephson junction

The Josephson junction: the active element of superconductive electronics



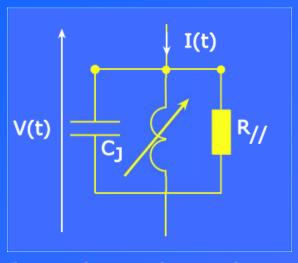
Most commonly used materials: Nb/Al-AlOx/Nb @ 4.2 K

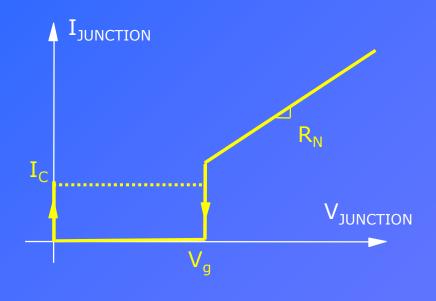


3 µm Pictures from the FLUXONICS Foundry - IPHT Jena - Germany



Josephson junction electrodynamics





$$I(t) = I_C(t) + I_J(t) + I_R(t)$$

$$I_J(t) = I_c \sin\varphi(t)$$

$$I_C(t) = C_J \frac{\partial V(t)}{\partial t}$$

$$I_R(t) = \frac{V(t)}{R_I}$$

2nd Josephson equation (Faraday's law): $V(t) = \frac{\Phi_0}{2\pi} \frac{\partial \Phi(t)}{\partial t}$

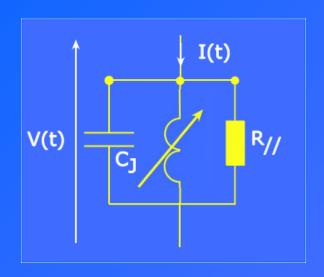
$$V(t) = \frac{\Phi_0}{2\pi} \left[\frac{1}{I_c \cos\varphi(t)} \frac{\partial I_J(t)}{\partial t} \right] = L_J \frac{\partial I_J(t)}{\partial t}$$

$$L_J = \frac{L_{J_0}}{\cos \varphi(t)}$$
 with $L_{J_0} = \frac{\Phi_0}{2\pi I_c}$ Josephson inductance

→ JJ = non-linear parallel RLC circuit



Josephson junction time constants



$$\frac{I(t)}{I_c} = L_{J_0} C_J \frac{\partial^2 \varphi(t)}{\partial t^2} + \frac{L_{J_0}}{R_{I/}} \frac{\partial \varphi(t)}{\partial t} + \sin \varphi(t)$$

Anharmonic oscillator

Electrical approach

Physical approach (BCS theory)

Plasma period of the L-C circuit:

$$\tau_p = 2\pi \sqrt{L_{J0}C_J}$$

$$\tau_p = \sqrt{\frac{2\pi\,\Phi_0 C_S}{j_C}}$$

L-R circuit time constant :

$$\tau_c = \frac{L_{J0}}{R_{II}}$$

$$\tau_c = \frac{2 \, \Phi_0}{\pi^2 \, V_{\perp}}$$

R-C circuit time constant:

$$\tau_{RC} = R_{II} C_{II}$$

$$\tau_{RC} = \frac{\pi V_{g} C_{S}}{4 j_{C}}$$

Minimizing the switching time

$$\tau_p = 2\pi \sqrt{L_{J0}C_J}$$

$$\tau_{LR} = \frac{L_{J0}}{R_{//}}$$

$$\tau_{RC} = R_{//} C_J$$

L-C circuit plasma period

L-R circuit time constant

R-C circuit time constant

McCumber parameter defined by:

$$eta_c = rac{ au_{RC}}{ au_{LR}} = rac{R_{//}^2 C_J}{L_{J_0}} = rac{2\pi R_{//}^2 C_J I_c}{\Phi_0}$$

Minimum switching time obtained for :

$$\tau_{RC} = \tau_{LR} \left(= \frac{\tau_p}{2\pi} \right) : \beta_c = 1$$

New time constant

$$\tau_0 = \sqrt{\frac{\Phi_0 C_S}{2\pi j_c}} = \frac{\Phi_0}{2\pi R_{shunt} I_c}$$

$$\tau_0(ps) \approx \frac{1}{\pi V_c(mV)} \text{ with } V_c = R_{shunt} I_c$$

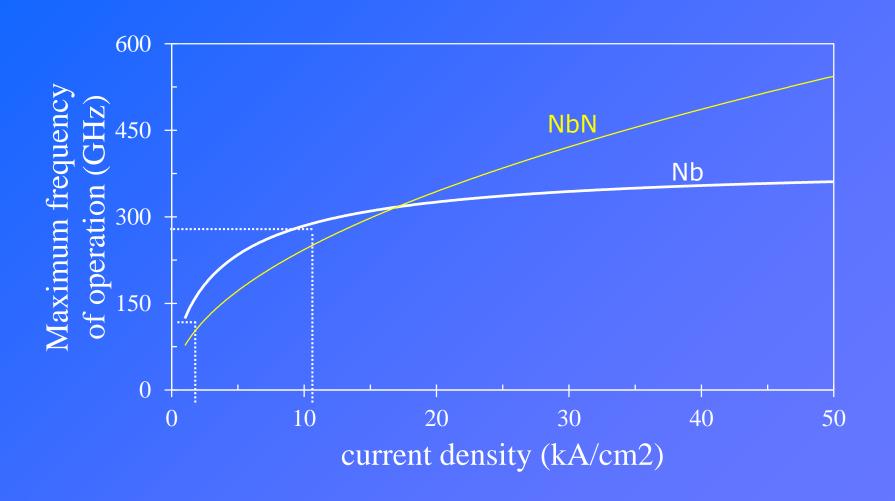
$$R_{//} \gg R_{shunt}$$

Criteria:
$$f_{max} = 1/(2\pi\tau_0)$$

$$f_{max}(GHz) = 500 \times V_c(mV)$$



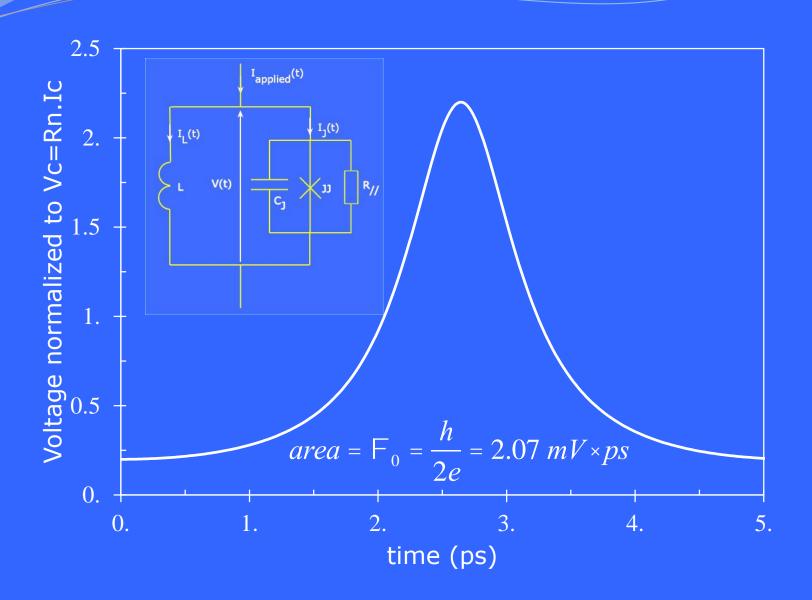
Maximum frequency of operation



Valid for externally-shunted SIS junctions



Rapid Single Flux Quantum (RSFQ) Logic



Superconducting electronics energy-delay product

$$EDP = \tau_0 I_c \Phi_0 = \frac{\Phi_0^2}{2\pi R_{shunt}} = \frac{6.10^{-31}}{R_{shunt}} J \cdot s$$

The EDP does not depend on the size of devices for externally-shunted junctions.

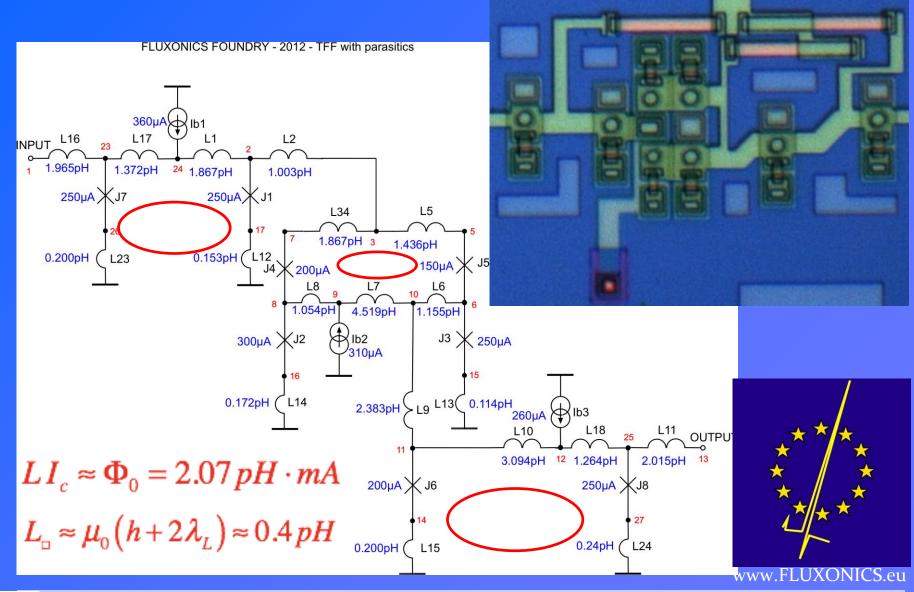
The EDP depends on the junction area for self-shunted junctions:

$$EDP \propto \frac{\Phi_0^2 A_{JJ}}{2\pi} \approx 10^{-30} \cdot A_{JJ} \left(\mu m^2\right) J \cdot s$$

$$EDP(semiconductors) = \frac{C^2 V_{dd}^3}{I_d}$$



SFQ cells





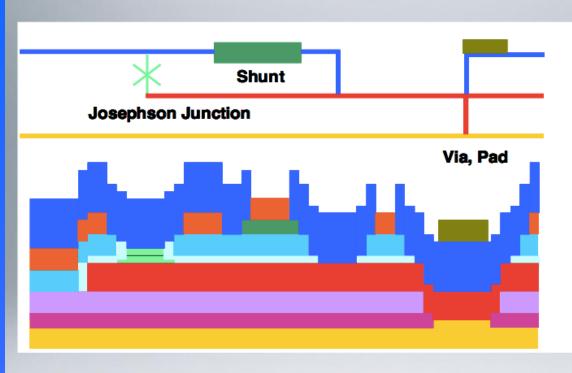
European FLUXONICS Foundry RSFQ process



RSFQ process - cross section



ıpht **zena**



Layer	Thickness	Material
R2	50 nm	Au
M2	350 nm	Nb
I2	150 nm	SiO
R1	80 nm	Мо
I1B	150 nm	SiO
I1A	70 nm	Nb ₂ O ₅
T1	60 nm 12 nm 30 nm	Nb Al ₂ O ₃ Nb
M1	250 nm	Nb
I0B	200 nm	SiO
I0A	50 nm	Nb ₂ O ₅
MO	200 nm	Nb

Via Josephson junction Shunt Via



Superconducting digital electronics foundry process

PROCESS	Current density [kA/cm²]	minimum area [μm²]	Maximum integration	Maximum frequency [GHz]
Hypres #03-10-45	0.03 1.0 4.5	~ 3.14	15,000	80 GHz RnIc=1.3mV @ 4.5 kA/cm ²
Hypres #S45/100/200	0.1 1 4.5 10 20 30	~ 0.4	10,000	200 GHz @ 30 kA/cm ²
MIT Lincoln Lab SFQx	10 20 50	~ 0.06	~ 800,000	240 GHz RnIc=2.17 mV @50 kA/cm ²
ADP2	10	1.0	1100 JJ/mm ²	80 GHz
STP2	2.5 - 20	0.25 - 4.0	100 JJ/mm ² - > 2,000 JJ/mm ²	30 GHz - 150 GHz
HSTP	10	1.0	70,000	80 GHz
Fluxonics standard	1	12.5	100 JJ/mm ²	40 GHz RnIc =0.256 mV
INRIM SNIS	up to 100	25	1,000 JJ/mm ²	300 GHz RnIc =0.1mV - 0.7mV
NIST Nb/Nbx Si1-x/Nb	up to 110	?	70,000	300 GHz
INRIM SNIS 3D FIB	up to 100	0.1	10,000 JJ/mm ²	300 GHz RnIc=0.1mV - 0.7mV



MIT Lincoln Lab foundry process



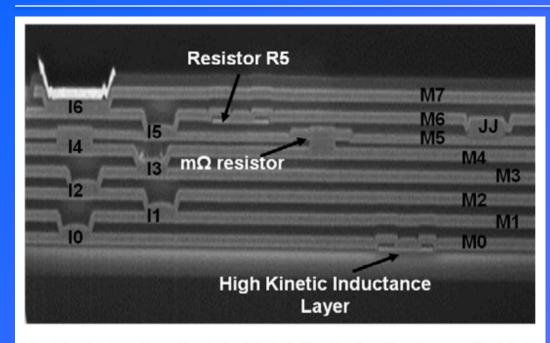
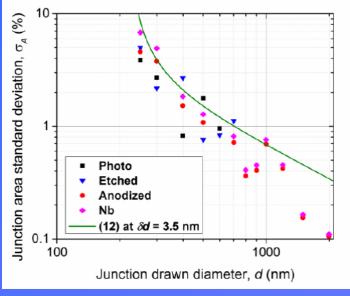
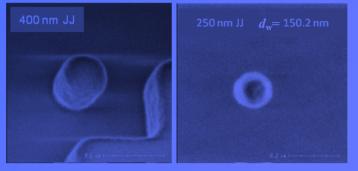


Fig. 10. Cross section of a wafer fabricated by the SFQ5ee process. The labels of metal layers and vias are the same as in Table I. New features of the SFQ5ee are shown: a high kinetic inductance layer under M0 and a layer of $m\Omega$ -range resistors between M4 and M5 layers.





JJ count $\approx 800,000$ JJ/chip

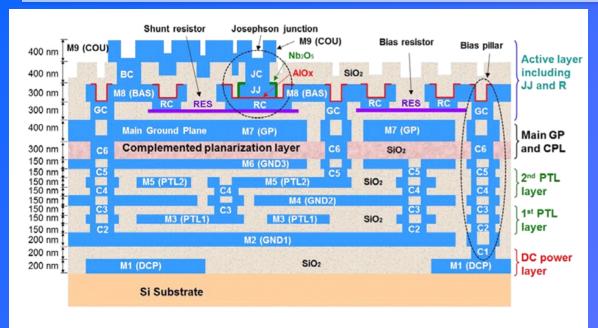
- S. K. Tolpygo et al, "Fabrication Process and Properties of Fully- Planarized Deep-Submicron Nb/Al-AlOx/Nb Josephson Junctions for VLSI Circuits," IEEE TAS 2015
- S.K. Tolpygo et al., "Developments towards a 250-nm, fully planarized fabrication process with ten superconducting layers and self-shunted Josephson junctions," arxiv_1704.07683 (20017); IEEE Trans. Appl. Supercond. to be published.



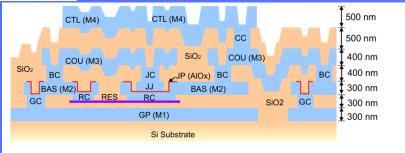


AIST foundry process





ADP 2 process (9 metal levels - 10kA/cm2)



STP2 process (4 metal levels - 2.5 or 20kA/cm2)

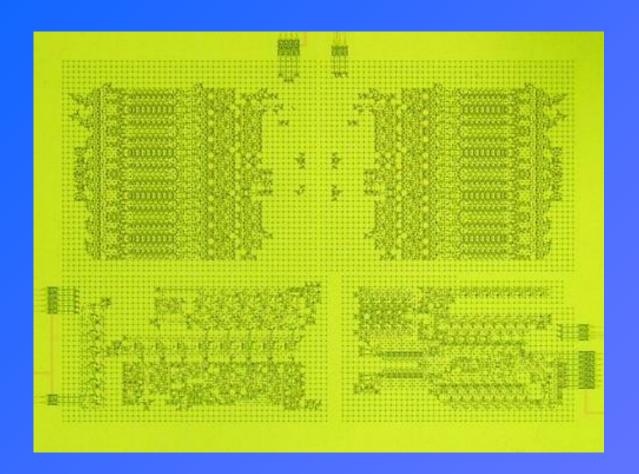
- S. Nagasawa et al., "Nb 9-Layer Fabrication Process for Superconducting Large-Scale SFQ Circuits and Its Process Evaluation," IEICE 2014
- S. Nagasawa, T. Satoh, and M. Hidaka, "Uniformity and Reproducibility of Submicron 20kA/cm2 Nb/AlOx/Nb Josephson Junction Process," ISEC 2015





Bit-serial μιχροπροχεσσορσ





COREe2 (2017) 10655 JJs

500 MIPS

2.4 mW

210 GIPS/W

Programs Executed

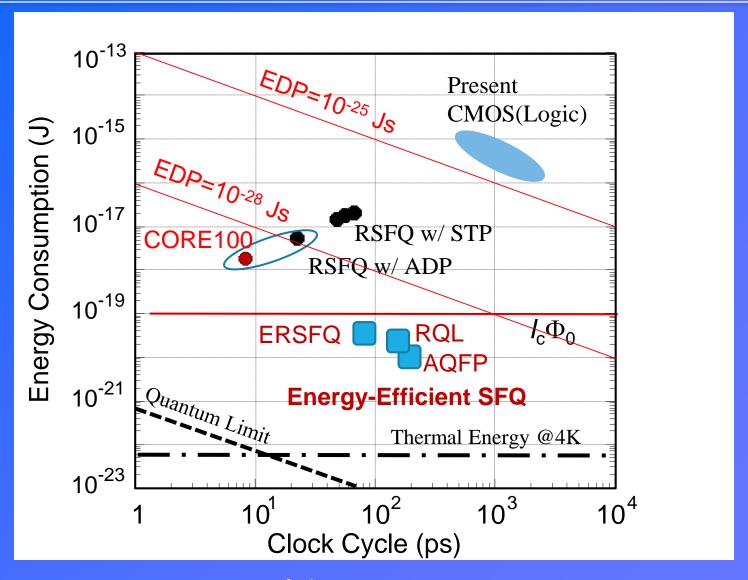
50 GHz

Memory Embedded

Courtesy: Prof. Akira FUJIMAKI - Nagoya University



Energetic considerations

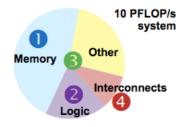


Courtesy: Prof. Akira FUJIMAKI - Nagoya University



Cryogenic Computer Complexity (C3) project - IARPA

Performance (PFLOP/s):	1	10	100	1,000
Power budget (@ 4 K)	1.5 w	10 w	100 w	1,000 w
Logic (RQL, Ic = 25 μA, 8.3 GHz) • processor cores	0.18 W • 40,200	1.8 W • 402,000	18 W • 4,020,000	180 W • 40,200,000
Memory (1 B/FLOP, JMRAM) • quantity (1 B/FLOPS)	0.46 W 1 PB	4.6 W 10 PB	46 W 100 PB	460 W 1,000 PB
Interconnects (VCSELs @ 40 K)	0.1 W	1 w	10 w	100 W
Other (structure, radiation heat leaks)	0.76 W	2.6 W	26 W	260 W
Total	1.5 W	10 W	100 W	1,000 W
• Computation efficiency (goal: ≥ 5 x 10 ¹¹ FLOPS/W)	0.7 x 10 ¹¹ FLOPS/W	2.5 x 10 ¹¹ FLOPS/W	5 x 10 ¹¹ FLOPS/W	5 x 10 ¹¹ FLOPS/W



Conclusions:

- Energy-efficient superconducting computers are possible
- Priorities:

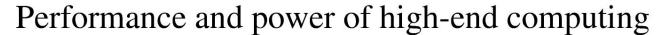
Memory → **Logic** → **System** → **Interconnects**



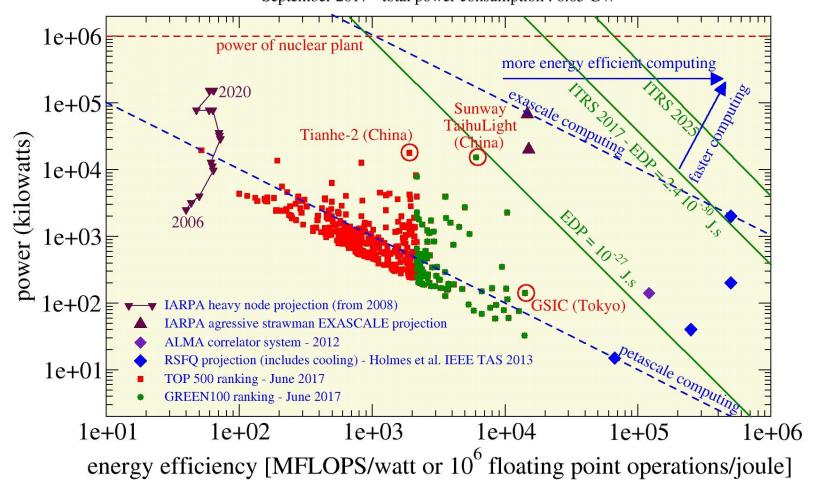
Source: Scott Holmes - Superconducting SFQ VLSI Workshop (SSV 2013) - November 2013



Comparaison of high-computing technologies



September 2017 - total power consumption: 0.65 GW





Cryogeny: Stirling cryocoolers

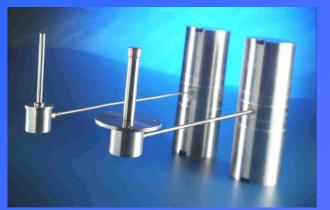
Long experience gained with tactical mini-coolers for infrared detection

Sliding rotating or linear pressure oscillator + mechanically or pneumatically driven cold expander: from a few 1000h up to a few 10.000h MTBF, ¼ to 2W @ 80K













Source: Alain Ravex -Absolut Systems



Superconducting digital electronics integrated systems



Complete cryocooled digital-RF receiver system prototype, assembled in a standard 1.8-meter tall 0.5-meter wide equipment rack.

Using the modular packaging approach, the system can currently host variety of chips.

The system includes a two-stage 4-K Gifford-McMahon cryocooler manufactured by Sumitomo, two sets of interface amplifiers for connecting chip outputs to an FPGA board (placed behind the vacuum enclosure, on the metal tray) for further digital processing and computer interface. The system also includes a current source and a temperature controller.

Courtesy of Deep Gupta - HYPRES



Commercially available 4K cryorefrigerators

Commercial 4K cryorefrigerators implementations:

 lubricated screw type helium compressors with oil

injection at suction and oil removal system at exhaust

- aluminum plate counter flow heat exchangers
- gas bearings frictionless cold expanders
- Typical characteristics:
 - automatic operation
 - efficiency: 20 25% of Carnot
 - turbines reliability: > 100.000h MTBF
 - cooling capacity/electrical input:

from 100W/50kW up to 1 kW/250kW @ 4K



Source: Alain Ravex - Absolut Systems



Lessons learnt for large cooling power from LTS high energy physics projects (i.e. CERN/LHC)

64 compressors (39MW_{elec}) 74 cold expansion turbines 28 cold compressors 1200 current leads 1800 sc magnets

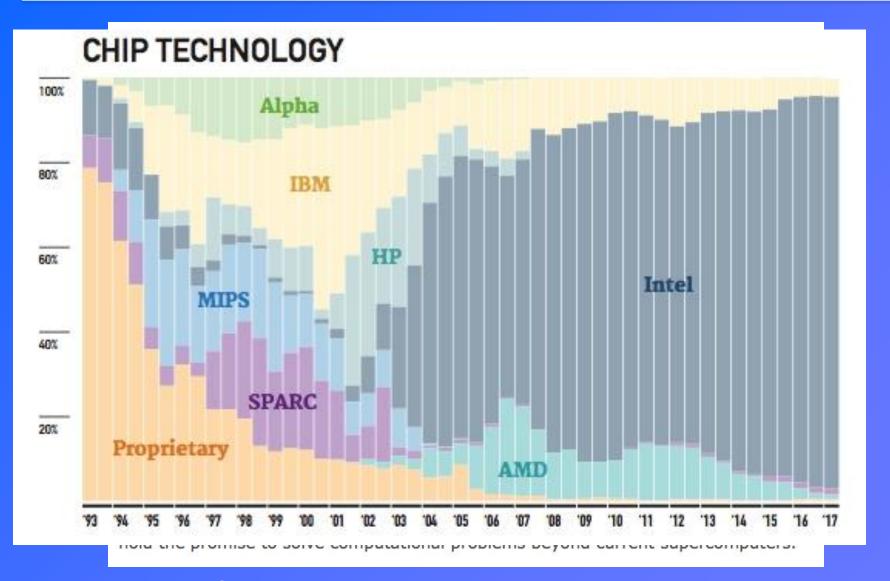
95% cryogenic system availability
30% Carnot efficiency

Industrial type operation with high efficiency, reliability and availability demonstrated for large cooling capacity 1.8K cryorefrigerators

Source: Alain Ravex - Absolut Systems



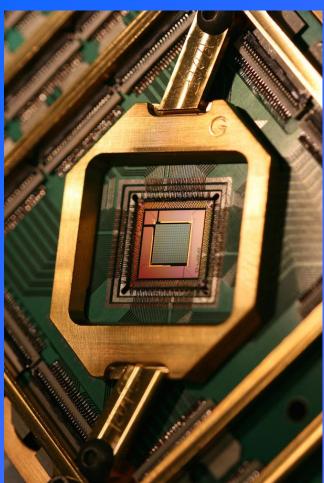
Next decade: how to proceed?



Source: https://ec.europa.eu/digital-single-market/en/high-performance-computing



Will next decade be quantum?







D-Wave's latest processor has 2,000 qubits — far surpassing the capacity of previous models.

Source: E. Gibney, "Quantum computer gets design upgrade," Nature, January 2017



Switching energies - speed

Technology	CMOS	superconducting digital electronics	quantum computing
temperature	300	4	0.04
thermal energy (J)	4.10 ⁻²¹	5.5.10 ⁻²³	5.5.10 ⁻²⁵
switching energy (J)	10 ⁻¹⁶	10 ⁻¹⁹	-
"thermal" frequency	6 THz	83 GHz	0.8 GHz



Cryogen free ultra low temperature coolers











Product name	lo	Triton 300	Triton 500	XL1000
Base Temperature	40 mK	10 mK	10 mK	3.3mK
cooling power at 10 mK				5 μW
cooling power at 20 mK		3 µW	12 µW	25 μW
cooling power at 100 mK	25 µW	300 µW	500 μW	1000 μW
Cooling power at 1K	200 mW	10 mW	10 mW	10 mW
Cooling power at 4K	1 W	1 W	1 W	3 W
Base plate for base temp (mm)	150	290	290	430
PTR type/number	1 W	1.5 W	1.5 W	2×1.5 W



From CMOS to quantum computers

	CMOS processing	superconducting processing	quantum processing
technology	мысторую крм (287000 крм) 128000 метор (28700 метор (287	CORE 1 - von 3	$\begin{array}{c} \bullet 0 \\ \downarrow \downarrow \\ 0 \\ \downarrow \downarrow \\ 0 \\ 1 \\ \hline \\ 0 \\ \downarrow 1 \\ \hline \\ 0 \\ \hline \\ 0 \\ \downarrow 1 \\ \hline \\ \end{array}$ Classical Bit Qubit
energy efficiency	10 ⁴ MFLOPS/W	5.10 ⁵ MFLOPS/W (includes cooling)	??
speed	2.4 GHz	100 GHz	problem-dependent
gates per cm ²	$2.64 \ 10^9$	$0.8\ 10^6$	2 10 ³
temperature of operation	300 K	4 K	0.01 K



Conclusion and prospectives

- Superconducting digital electronics has achieved some major breakthroughs during the last decade that enables the fabrication of superconducting microprocessors today (Core e2, Core e4) through energy-efficient biasing techniques and higher integration.
- Some challenges are still ahead :
 - memory issue
 - further integration required by down-sizing gates: higher square inductances (NbN, thicker films), narrower line widths (down to what values?), 3D integration.
 - design tools for complex circuits need be developed
- Some prospectives :
 - other materials need more investigation, either for JJ or/and for interconnects: NbN, MgB2
 - a small increase of temperature of operation would be of great help for energy budget $(4K \rightarrow 10K \rightarrow 20K)$
 - exascale objective may not be ambitious enough regarding semiconductors advances : a larger cryogenic system is more energy-efficient.
 - Superconducting digital electronics is a natural interface between room-temperature semiconductors electronics and quantum computing systems

